

Form PTO-1449 (Modified)

LIST OF PATENTS AND PUBLICATIONS
FOR APPLICANT'S
INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Atty Docket No.

PRMSP0300US

Serial No.

10/757,119

Applicant: Wu et al.

Filing Date

01/14/04

Group

U.S. PATENT DOCUMENTS

Examin Initial	Document Number	Date (MM/YYYY)	Name	Class	Subclass	Filing Date if Appropriate
R.A.	4,857,426	08/1989	Bott et al.	430	18	
	5,087,677	02/1992	Brekner et al.	526	160	
	5,324,801	06/1994	Brekner et al.	526	160	
	5,371,158	12/1994	Brekner et al.	526	127	
	5,422,409	07/1995	Brekner et al.	526	281	
	5,468,819	11/1995	Goodall et al.	526	171	
	5,569,730	10/1996	Goodall et al.	526	282	
	5,571,881	11/1996	Goodall et al.	526	171	
	5,602,219	02/1997	Aulbach et al.	526	160	
	5,605,726	02/1997	Gibbons et al.	428	1	
	5,637,400	06/1997	Brekner et al.	428	137.3	
	5,663,308	09/1997	Gibbons et al.	534	573	
	5,698,645	12/1997	Weller et al.	526	160	
	5,714,304	02/1998	Gibbons et al.	430	270.11	
	5,733,991	03/1998	Rohrmann et al.	526	160	
	5,760,139	06/1998	Koike et al.	525	200	
	5,783,636	07/1998	Koike et al.	525	199	
	5,881,201	03/1999	Khanarian et al.	385	146	
	5,916,971	06/1999	Koike et al.	525	197	
	6,057,466	05/2000	Starzewski et al.	556	19	
	6,121,340	09/2000	Shick et al.	522	31	
	6,136,499	10/2000	Goodall et al.	430	270.1	
	6,166,125	12/2000	Sugiyama et al.	524	462	
R.A.	6,169,052 B1	01/2001	Brekner et al.	502	152	

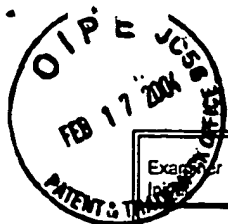
Examiner Initial	Document Number	Date (MM/YYYY)	Name	Class	Subclass	Filing Date If Appropriate
P.A.	6,183,934 B1	02/2001	Kawamoto et al.	430	270.1	
	6,197,984 B1	03/2001	Makovetsky et al.	556	146	
	6,214,951 B1	04/2001	Brekner et al.	526	160	
	6,232,417 B1	05/2001	Rhodes et al.	526	171	
	6,265,131 B1	07/2001	Chang et al.	430	270.1	
	6,284,429 B1	09/2001	Kinsho et al.	430	270.1	
	6,294,616 B1	09/2001	Rhodes et al.	525	332.1	
	6,538,087 B2	03/2003	Zhao et al.	526	280	
P.A.	2003/0176583	09/2003	Rhodes et al.	525	326.2	

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date (MM/YYYY)	Country	Class	Sub-class	Translation	
						Yes	No
✓ P.A.	96/37528	11/1996	WO				
✓	00/20472	04/2000	WO				
✓	00/24726	05/2000	WO				✓
✓	00/34344	06/2000	WO				
RA ✓	0 445 755 A2	09/1991	EP				

OTHER ART

Examiner Initial	Author, Title, Date, Pertinent Pages, etc.
OA	Uetani et al.; "Positive ArF resist with 2eAdMA/GBLMA resin system"; SPIE Conference on Advance Resist Technology and Processing XVI, 1999; SPIE Vol. 3678; pp. 510-513.
	Nozaki et al.; "New Protective Groups in Alicyclic Methacrylate Polymers for 193-nm Resists"; <i>Journal of Photopolymer Science and Technology</i> ; Vol. 10, No. 4; 1997; pp. 545-550.
	Chan et al.; "New Chiral Sultam Auxiliaries: Preparation and Their Application in Asymmetric Diels-Alder Reactions"; <i>Tetrahedron: Asymmetry</i> ; Vol. 8, No. 15; pp. 2501-2404; 1997.
	Brodsky et al.; "157 nm Resist Materials: Progress Report"; <i>J. Vac. Sci. Technol. B</i> 18(6); Nov./Dec. 2000; pp. 3396-3401.
	Hung et al.; "Resist Materials for 157 nm Microlithography: An Update"; <i>Proceedings of the SPIE</i> , Vol. 4345; Conference held in Santa Clara, CA 2/2001.
OA	Chiba et al.; "157 nm Resist Materials: A Progress Report"; <i>Journal of Photopolymer Science and Technology</i> ; Vol. 13, No. 4; 2000; pp. 657-664.



Examiner	Author, Title, Date, Pertinent Pages, etc.
RA	Patterson et al.; "Polymers for 157 nm Photoresist Applications: A Progress Report"; Proc. of SPIE; Vol. 3999, Advances in Resist Technology and Processing XVII, 2000.
EA	Hung et al.; "Synthesis of Alicyclic Polymers for 157 nm Photoresists by PD ²⁺ Catalyzed Vinyl Addition Polymerization"; California Institute of Technology, Posted March 14, 2003.

EXAMINER	2. AskM	DATE CONSIDERED	9-6-05
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Information Disclosure Statement PTO-1449 (Modified)

The identification of any reference is not intended to be, and should not be understood as being, an admission that such publication, in fact, constitutes "prior art" within the meaning of applicable law since, for example, a given reference may have a later effective date than first seems apparent or the reference may have an effective date which can be antedated. The "prior art" status of any reference is a matter to be resolved during prosecution.

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